

*Patent Quality Connotation and its Measuring Indicator System:  
The Patent Quality Comparison Between China and the Main Developed Countries  
Based on SIPO's Patent Data*

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This paper develops an indicator system to measure patent quality, which is defined as the degree of meeting statutory requirements of patentability and sufficient disclosure of technical information. Patent quality is divided into three dimensions: technological, legal and economic dimensions and it can be measured from four aspects: technology quality, application file quality, examination quality, and economic quality. To operationalize each aspect, several secondary indicators and third-level indicators are developed. The research tries to integrate theory and practice, the indicators selected considers both theoretical completeness and data accessibility. Intended to find out the relative position of China's patent quality in the globe, this paper compares the four aspects of patent quality of eight developed countries, and discovered that many criticism towards China's patent quality based on surveys is not reliable, examination quality is actually the best performed aspects of China's patent quality, while for technology, application file and economic quality, China is really far behind those developed countries.

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